

UNITED STATES DEPARTMENT OF COMMERCE Patent and Train ark Office

• ;	Addres	ss: COMMISSIOn of OF PATENTS AND TRADEMARKS Washington, D.C. 20231
	PPLICATION NUMBER FILING DATE FIRST NAMED APPLIC	ANT V 2686 CAFTIX OCCAPET NO.
	15 (55 /OE GIN	2000 ON 13 COURT NO.
0875	538,073 10/02/33 556	
• •		EXAMINER
•	21M1/0616	EVANS, G
STOE	DEL RIVES	
900	O SW FIFTH AVENUE	ART UNIT PAPER NUMBER
COLT 1	TTE 2300	2106
PORT	RTLAND OR 97204-1268	_{06/16/97} <i>0</i>
		DATE MAILED:
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	Is a communication from the examiner in charge of your application. MISSIONER OF PATENTS AND TRADEMARKS	
	OFFICE ACTION SUMM	MARY
Respo	ponsive to communication(s) filed on	
☐ This a	action is FINAL.	
	be this application is in condition for allowance except for formal matters, ordance with the practice under Ex parte Quayle, 1935 D.C. 11; 453 O.G.	
A abadana		The state of the s
whichever	ned statutory period for response to this action is set to expire er is longer, from the mailing date of this communication. Failure to responsition to become abandoned. (35 U.S.C. § 133). Extensions of time mailing date of the properties of time mailing the properties of the prope	
Dispositio	tion of Claims	
x 1	l = 22	
		is/are pending in the application.
 -	7 17	is/are withdrawn from consideration.
Claim(10 71	is/are allowed.
Claim(is/are rejected.
Claim(m(s)	
	tion Papers	are subject to restriction of election requirement.
See th	the attached Notice of Draftsperson's Patent Drawing Review, PTO-948.	
	•	re objected to by the Examiner.
	proposed drawing correction, filed on	is _ approved _ disapproved.
	specification is objected to by the Examiner.	
	oath or declaration is objected to by the Examiner.	
_	under 35 U.S.C. § 119	
Ackno	nowledgment is made of a claim for foreign priority under 35 U.S.C. § 119	9(a)-(d).
☐ Ali	NI Some* None of the CERTIFIED copies of the priority doc	uments have been
☐ re	received.	
re	received in Application No. (Series Code/Serial Number)	
re	received in this national stage application from the International Bureau	(PCT Rule 17.2(a)).
*Certifie	fied copies not received:	
Acknow	nowledgment is made of a claim for domestic priority under 35 U.S.C. § 1	19(e).
Attachmer	ent(s)	
Notice	ce of Reference Cited, PTO-892	
	rmation Disclosure Statement(s), PTO-1449, Paper No(s). 2/3/15/6	7
	view Summary, PTO-413	
1 _	ce of Draftnerson's Patent Drawing Review PTO-948	

-SEE OFFICE ACTION ON THE FOLLOWING PAGES--

PTOL-326 (Rev. 9/96)

Notice of Informal Patent Application, PTO-152

Serial Number: 08/538,073

Art Unit: 2106

DETAILED ACTION

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(f) or (g) prior art under 35 U.S.C. 103(a).

2. Claims 12-21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lapham et al. in view of Dow et al. and Mueller. Lapham et al. in U.S. Patent No. 4,399,345 discloses laser trimming a resistor on a silicon substrate with a wavelength of 1.34 microns, which Applicant has disclosed as being within Applicant's third wavelength range. Lapham does not disclose the circuitry for measuring an operational parameter of the device, nor a beam positioner. Dow et al. in the article "Reducing Post-Trim Drift of Thin Film Resitors (sic) by Optimizing YAG laser Output Characteristics" teaches using an osscilloscope to measure resistance of a resistor during a functional laser trimming process. Mueller in the article "Functional laser trimming of thin film resistors on Silicon ICs" on the first paragraph of page 72 teaches an apparatus to scan the beam. It would have been obvious to adapt Lapham et al. in view of Dow et al., and Mueller to

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provide this to functionally laser trim a resistor on a silicon substrate Regarding claim 13, using a computer to compare resistance readings and control a process is old and well known and official notice is taken of the same. It would have been obvious to adapt Lapham et al. in view of Dow et al. to provide this to computer control the process, permitting software adjustments to the process.

- 3. Claim22 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 4. Claims 1- 11 are allowed over the prior art of record.
- 5. The following is an examiner's statement of reasons for allowance: Leong et al. in U.S. Patent No. 5,611,946 uses various wavelengths from a laser to cut various materials at a probe station. Dow et al. in the article "Reducing Post-Trim Drift of Thin-Film Resitors by Optimizing YAG Laser Output Characteristics" discusses using a second harmonic generator generating 532nm from a 1064nm YAG laser to trim resistors to investigate its effect on post-trim depth. Regarding claims 1-11, none of the references of record teaches or suggests, alone or in combination, the method for modifying with laser output a measurable operational parameter of an activated electronic device while preventing a spurious optoelectronic response in the device, the device having a target material with sensitivity to laser output in a first wavelength range and nontarget material having optoelectronic sensitivity in a second wavelength range that forms a subset of the first wavelength range such that exposure to a wavelength within the second wavelength range causes spurious optoelectronic effects in the non-target material, determining a third wavelength range of laser output for which the non-target material has substantial optoelectronic insensitivity, the third wavelength range excluding the second wavelength range; activating the device; sending a laser pulse with a wavelength within both the first and third wavelength regions to ablate a portion of the target material; and measuring within the time interval a true value of the operational parameter of the device. In particular while Lapham et al.

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in U.S. Patent 4,399,345 uses a laser wavelength of 1.34 microns to laser trim resistors on a silicon substrate and in column 3, lines 4-7 teaches using wavelengths greater than 1.065 microns as the substrate becomes more "transparent" to prevent heat damage, Lapham does not disclose determining the second wavelength region.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

- 6. The status of Serial No. 08/343,779 on the first page of the specification should be updated.
- Any inquiry concerning this communication or earlier communications from the examiner 7. should be directed to Geoff Evans whose telephone number is (703) -308-1653.

GSE

June 9, 1997

GEOFFREY S. EVANS PRIMARY EXAMINER

Deoffrey S, Evans

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